

Status of Irradiations DEPFETs and MOS diodes

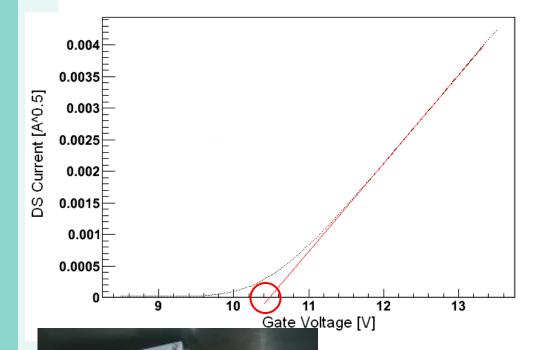
Carried out at the x-ray facility of KIT by

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Andreas Ritter



DEPFET: Measurement of threshold voltage shift



Up: Typical extraction of threshold voltage from $I_{DS} - V_{G}$ data.

Down: X-ray tube at the Karlsruhe Irradiation center.

From: [http://www-ekp.physik.uni-karlsruhe.de/index.php?option=com_content&view=article&id=93&Itemid=12&lang=de]

- 2 Devices under Test
- Irradiation scheme:
 - DUT 1: Zero Voltage at Gate contact
 - DUT 2: Adaptive biasing from Off voltage (5V) to zero voltage at Gate contact
- Threshold voltage via I_{DS}
 V_G measurement
- Mini matrices from PXD5
- X-ray irradiation carried out in Karlsruhe

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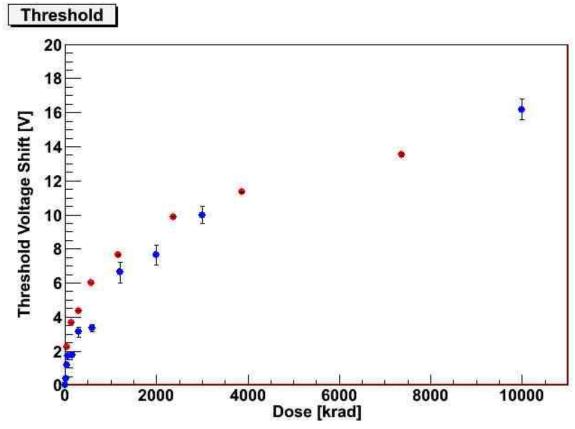


DEPFET: Results of threshold voltage shift

Observation and conclusions:

Breakdowns:

- Short circuit current between layers Poly 1 and Poly 2 with DUT 1 prevented further measurements at higher doses (>7.5 Mrad)
- 2. DUT still lived after 10 Mrad
- Voltage shift of about 16.5 V at 10 Mrad
- Annealing of threshold voltage shift after approx.
 500 h is around 4 V
- Threshold voltage spread over several pixels is under investigation

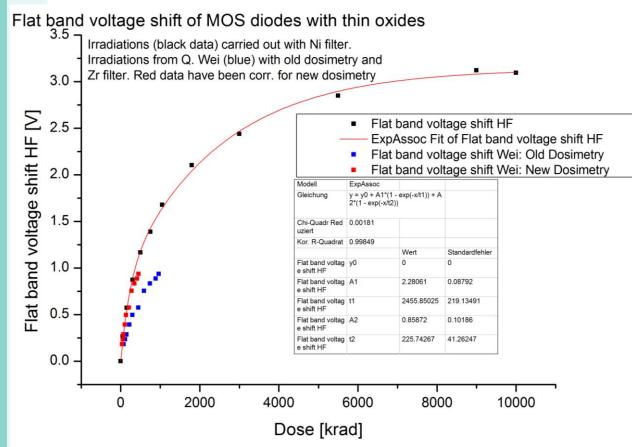


Red: DUT 1 Blue: DUT 2

Measurement done by P. Müller. Voltage errors are based on standard deviation of threshold voltage shifts of 6 pixels.



MOS diodes: Flat band voltage shift



Tasks:

- Irradiate MOS diode up to 10 Mrad
 - Evaluate flat band voltage shift
 - Compare results with data of Q. Wei

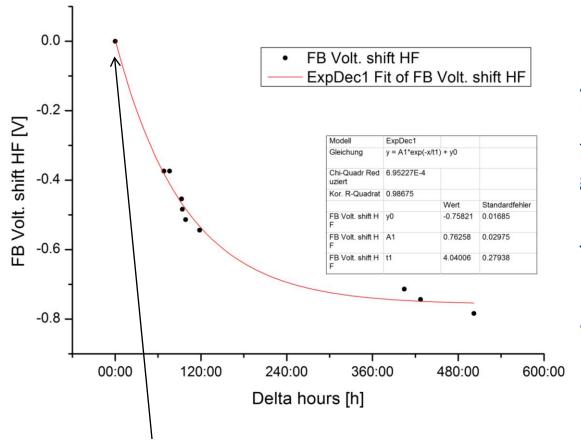
Conclusions:

- Corrected data from Q.
 Wei corresponds well
 with new dosimetry
- Fit model seems to agree fine, but has yet to be evaluated

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MOS diodes: Annealing of flat band voltage shift



Annealing is still under investigation, but so far, the threshold voltage shift is in good shape

To be done:

Evaluate interface traps and annealing of them

Flat band voltage value at 10 Mrad is set to "0"